Electronic Supplementary Material (ESI) for Journal of Materials Chemistry C. This journal is © The Royal Society of Chemistry 2021

Supporting Information

Switchable Multimode Microlaser based on AIE Microsphere

Fengyan Song, Chunhuan Zhang, Haiyun Dong, Yuqin Fan, Ming-Yu Wu, Guogang Shan, Puxiang Lai, Hui Gao*, Yong Sheng Zhao*, Sijie Chen*

Dr. F. Song, Prof. H. Gao

School of Aeronautic Science and Engineering, Beihang University, Beijing 100191, China

E-mail: <u>h.gao@buaa.edu.cn</u>

Dr. C. Zhang, Dr. H. Dong, Dr. Y. Fan, Prof. Y. S. Zhao

Key Laboratory of Photochemistry, Institute of Chemistry, Chinese Academy of Sciences, Beijing

100190, China

E-mail: yszhao@iccas.ac.cn

Prof. H. Gao , Dr. M-Y, Wu, Dr. S, Chen

Ming Wai Lau Centre for Reparative Medicine, Karolinska Institutet, Hong Kong, China.

E-mail: sijie.chen@ki.se

Dr. G. Shan

Institute of Functional Material Chemistry, Faculty of Chemistry, Northeast Normal University, Renmin

Road 5268, Changchun 130024, P.R. China.

Dr. P. Lai

Department of Biomedical Engineering, The Hong Kong Polytechnic University, Hong Kong, China



Figure S1. a) Normalized UV-Vis spectra of ASCPI in different solvents. b) Normalized emission spectra of ASCPI in different solvents.



Figure S2. PL spectra of ASCPI and ASCPI@starch in water. (10⁻⁵ mol/L, excitation: 460 nm)



Figure S3. Lasing intensity as a function of pulse number.



Figure S4. Fourier transform infrared spectra of the ASCPI under alternate exposure to HAc, NH₃ and air.



Figure S5. (a) PL images of an ASCPI@starch microsphere under alternate exposure to HAc and air. Scale bars: 20 µm. (b–c) Wavelength shift of lasing modes in the ASCPI@starch microsphere 1 (b), 2 (c) under alternate exposure to HAc and air, respectively.



Figure S6. (a) PL image of an ASCPI@starch microsphere under alternate exposure to NH₃ and air. Scale

bars: 20 μ m. (b–c) Wavelength shift of lasing modes in the ASCPI@starch microsphere **1** (b), **2** (c) under alternate exposure to NH₃ and air, respectively.



Figure S7. XRD patterns of the ASCPI@starch microspheres under alternate exposure to HAc, NH₃ and air.

	λ_{em}^{a}	τ ^{b)}	${\it \Phi}_{\rm PL}{}^{ m c)}$	$k_{\rm r}^{\rm d}$	$k_{\rm nr}^{\rm d}$
	[nm]	[ns]	[%]	[ns ⁻¹]	[ns ⁻¹]
Pristine	638	1.41	14.7	0.1043	0.6050
HAc	633	1.03	10.6	0.1029	0.8080
NH ₃	646	1.30	7.6	0.0585	0.7108

Table S1. Photophysical properties of the microspheres under alternate exposure to air, HAc and NH₃.

Abbreviation: ^{a)} Emission peak, ^{b)} Fluorescence lifetime, ^{c)} Φ_{PL} = photoluminescence quantum yield, determined using an integrating sphere, ^{d)} $k_r = \Phi/\tau$ and $k_{nr} = (1 - \Phi)/\tau$, k_r = radiative decay rate constant, k_{nr} = non-radiative decay rate constant.